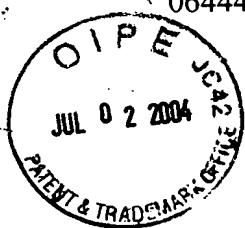


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PATENT APPLICATION  
10/044,076



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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: H. Ufuk Alpay et al.

Serial No.: 10/044,076

Date Filed: January 11, 2002

Group Art Unit: 1756

Examiner: Mohamedulla, Saleha R.

Title: **DAMAGE RESISTANT PHOTOMASK  
CONSTRUCTION**

**MAIL STOP – AF**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited with the United States Postal Service as Express Mail No. EV351292059US addressed to: Mail Stop – AF, Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on July 2, 2004.

  
\_\_\_\_\_  
Jay Howard

Dear Sir:

**RESPONSE TO FINAL OFFICE ACTION**

In response to the Final Office Action mailed May 5, 2004, Applicants respectfully submit the following amendments set forth below and request favorable action thereon.

**Amendments to Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 7 of this paper.